

## CLAIMS

What is claimed is:

- 1 1. A method comprising:  
2 determining a location of one or more regions on a reticle that come in contact  
3 with a reticle handling or support surface; and  
4 generating a pattern to be written on the reticle, the pattern including one or  
5 more cut-out regions corresponding to the one or more regions that have been  
6 determined to come in contact with the reticle handling or support surface.
- 1 2. The method of claim 1, wherein determining a location of the one or more  
2 regions comprises determining a type of support surface used for the reticle.
- 1 3. The method of claim 1, wherein determining a location of the one or more  
2 regions comprises determining a type of carrier used for the reticle.
- 1 4. The method of claim 1, wherein determining a location of the one or more  
2 regions comprises determining a type of handling apparatus used for the reticle.
- 1 5. The method of claim 1, wherein determining a location of the one or more  
2 regions comprises determining a type of storage apparatus used for the reticle.
- 1 6. The method of claim 1, wherein determining a location of the one or more  
2 regions comprises determining a manufacturing process used with the reticle.

1 7. The method of claim 6, wherein determining a location of the one or more  
2 regions comprises determining one or more required features to be written on the  
3 reticle.

1 8. The method of claim 1, further comprising determining a size of each cut-out  
2 region.

1 9. The method of claim 1, further comprising writing the pattern on a reticle blank.

1 10. The method of claim 9, further comprising developing and etching the pattern  
2 to remove reticle surface chrome from the regions that have been determined to  
3 come in contact with the reticle handling or support surface.

1 11. A reticle comprising: ✓  
2 a circuit pattern to be exposed on a wafer; and  
3 one or more chrome cut-out regions positioned where a reticle handling or  
4 support apparatus has been determined to come in contact with the reticle.

1 12. The reticle of claim 11, further comprising a barcode.

1 13. The reticle of claim 11, further comprising an alignment feature.

1 14. The reticle of claim 11, further comprising a pellicle to shield the reticle from  
2 particles.

1 15. The reticle of claim 11, further comprising a reticle manufacturing structure.

1 16. A method comprising:  
2 writing a pattern on a blank reticle having a layer of photoresist and a layer of  
3 chrome, the pattern including one or more cut-out regions that have been  
4 determined to come in contact with a reticle handling or support apparatus;  
5 developing the pattern to remove the photoresist layer and reveal the chrome  
6 layer in the regions determined to come in contact with the reticle handling or  
7 support apparatus; and  
8 etching away the chrome layer to remove chrome from the regions  
9 determined to come in contact with the reticle handling or support apparatus.

1 17. The method of claim 16, wherein the layer of photoresist is positive and  
2 developing the pattern comprises exposing and removing the photoresist layer from  
3 the written regions to reveal the chrome layer.

1 18. The method of claim 17, wherein etching away the chrome layer comprises  
2 etching away the chrome layer from the written regions to reveal a glass layer of the  
3 reticle.

1 19. The method of claim 16, wherein the layer of photoresist is negative and  
2 developing the pattern comprises exposing and removing the photoresist layer from  
3 the unwritten regions to reveal the chrome layer.

1 20. The method of claim 19, wherein etching away the chrome layer comprises  
2 etching away the chrome layer from the unwritten regions to reveal a glass layer of  
3 the reticle.

1 21. The method of claim 16, wherein writing a pattern on a blank reticle comprises  
2 writing a pattern on a blank reticle via an E-beam machine.

1 22. The method of claim 16, wherein writing a pattern on a blank reticle comprises  
2 writing a pattern on a blank reticle via a laser writer.